

Takashi Egawa

List of Publications by Year in descending order

Source: <https://exaly.com/author-pdf/2554962/publications.pdf>

Version: 2024-02-01

41
papers

1,938
citations

471509

17
h-index

302126

39
g-index

41
all docs

41
docs citations

41
times ranked

1953
citing authors

#	ARTICLE	IF	CITATIONS
1	The role of p-GaN layer thickness for the evaluation of high-performance and ultrafast GaInN/GaN multiple quantum wells UV photodetectors. <i>Optical Materials</i> , 2022, 127, 112284.	3.6	5
2	Reduced nonradiative recombination rates in <i>c</i> -plane Al _{0.83} In _{0.17} N films grown on a nearly lattice-matched GaN substrate by metalorganic vapor phase epitaxy. <i>Applied Physics Letters</i> , 2021, 119, .	3.3	5
3	Improved epilayer qualities and electrical characteristics for GaInN multiple-quantum-well photovoltaic cells and their operation under artificial sunlight and monochromatic light illuminations. <i>AIP Advances</i> , 2021, 11, .	1.3	4
4	Mass production-ready characteristics of AlGaIn/AlN/GaN high-electron-mobility transistor structures grown on 200 mm diameter silicon substrates using metal-organic chemical vapor deposition. <i>Semiconductor Science and Technology</i> , 2021, 36, 014004.	2.0	5
5	Metalorganic Chemical Vapor Deposition of over 150-nm-thick Quaternary AlGaInN Epitaxial Films near Alloy Composition Lattice-Matching to GaN on Sapphire and Their Structural and Optical Characterization. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2020, 217, 1900597.	1.8	4
6	Correlation between structural properties and nonradiative recombination behaviors of threading dislocations in freestanding GaN substrates grown by hydride vapor phase epitaxy. <i>CrystEngComm</i> , 2020, 22, 8299-8312.	2.6	13
7	Investigation of AlGaIn/GaN high electron mobility transistors on Silicon (111) substrates employing multi-stacked strained layer superlattice structures. <i>Superlattices and Microstructures</i> , 2020, 147, 106709.	3.1	13
8	Epitaxial regrowth and characterizations of vertical GaN transistors on silicon. <i>Semiconductor Science and Technology</i> , 2019, 34, 095013.	2.0	2
9	A 300 nm thick epitaxial AlInN film with a highly flat surface grown almost perfectly lattice-matched to <i>c</i> -plane free-standing GaN substrate. <i>Japanese Journal of Applied Physics</i> , 2019, 58, SC1006.	1.5	19
10	Effect of threading dislocation in an AlN nucleation layer and vertical leakage current in an AlGaIn/GaN high-electron mobility transistor structure on a silicon substrate. <i>Semiconductor Science and Technology</i> , 2019, 34, 035015.	2.0	9
11	Microstructure variation in thick AlInN films grown on <i>c</i> -plane GaN on sapphire by metalorganic chemical vapor deposition. <i>Journal of Crystal Growth</i> , 2019, 506, 40-44.	1.5	33
12	Epitaxial growth and characterization of approximately 300-nm-thick AlInN films nearly lattice-matched to <i>c</i> -plane GaN grown on sapphire. <i>Applied Physics Express</i> , 2018, 11, 051001.	2.4	26
13	A Comparative Study of InGaIn/GaN Multiple-Quantum-Well Solar Cells Grown on Sapphire and AlN Template by Metalorganic Chemical Vapor Deposition. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2018, 215, 1700323.	1.8	6
14	The 2018 GaN power electronics roadmap. <i>Journal Physics D: Applied Physics</i> , 2018, 51, 163001.	2.8	843
15	Dynamic variation of carrier transport properties of recessed Au-free ohmic contacts to InAlN/AlN/GaN on Si-wafer. <i>Japanese Journal of Applied Physics</i> , 2018, 57, 110302.	1.5	3
16	Enhancement of breakdown voltage for fully-vertical GaN-on-Si p-n diode by using strained layer superlattice as drift layer. <i>Semiconductor Science and Technology</i> , 2018, 33, 065017.	2.0	5
17	Al ₂ O ₃ /AlGaIn Channel Normally-Off MOSFET on Silicon With High Breakdown Voltage. <i>IEEE Electron Device Letters</i> , 2017, 38, 497-500.	3.9	16
18	Analysis of carrier trapping and emission in AlGaIn/GaN HEMT with bias-controllable field plate. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2017, 214, 1600840.	1.8	5

#	ARTICLE	IF	CITATIONS
19	Effect of well layer thickness on quantum and energy conversion efficiencies for InGaN/GaN multiple quantum well solar cells. <i>Solid-State Electronics</i> , 2017, 129, 29-34.	1.4	16
20	Effect of Drift Layer on the Breakdown Voltage of Fully-Vertical GaN-on-Si p-n Diodes. <i>IEEE Electron Device Letters</i> , 2017, 38, 1720-1723.	3.9	26
21	Impact of the AlN nucleation layer on the variation of the vertical-direction breakdown voltage of AlGaIn/GaN high-electron-mobility transistor structures on a Si substrate. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2017, 214, 1600843.	1.8	11
22	Growth of rough-surface p-GaN layers on InGaIn/GaN multiple-quantum-well structures by metalorganic chemical vapor deposition and their application to GaN-based solar cells. <i>Materials Research Express</i> , 2017, 4, 085904.	1.6	8
23	Effect of the formation temperature of the AlN/Si interface on the vertical-direction breakdown voltages of AlGaIn/GaN HEMTs on Si substrates. <i>MRS Advances</i> , 2016, 1, 3415-3420.	0.9	4
24	Analysis of reaction between c+a and -c+a dislocations in GaN layer grown on 4-inch Si(111) substrate with AlGaIn/AlN strained layer superlattice by transmission electron microscopy. <i>AIP Advances</i> , 2016, 6, .	1.3	7
25	Device characteristics and performance estimation of nearly lattice-matched InAlN/AlGaIn heterostructure field-effect transistors. <i>Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics</i> , 2016, 34, 050602.	1.2	13
26	Modeling of the wafer bow in GaN-on-Si epiwafers employing GaN/AlN multilayer buffer structures. <i>Semiconductor Science and Technology</i> , 2016, 31, 105016.	2.0	18
27	Novel fully vertical GaN p-n diode on Si substrate grown by metalorganic chemical vapor deposition. <i>Applied Physics Express</i> , 2016, 9, 111005.	2.4	31
28	Improved performance of InGaIn/GaN multilayer solar cells with an atomic layer deposited Al ₂ O ₃ passivation film. <i>Electronics Letters</i> , 2016, 52, 1246-1248.	1.0	3
29	Influence of AlN nucleation layer on vertical breakdown characteristics for GaN-on-Si. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2016, 213, 424-428.	1.8	39
30	Enhanced two dimensional electron gas transport characteristics in Al ₂ O ₃ /AlInN/GaN metal-oxide-semiconductor high-electron-mobility transistors on Si substrate. <i>Applied Physics Letters</i> , 2015, 107, .	3.3	14
31	Uniform Growth of AlGaIn/GaN High Electron Mobility Transistors on 200 mm Silicon (111) Substrate. <i>Applied Physics Express</i> , 2013, 6, 026501.	2.4	89
32	1.4-kV Breakdown Voltage for AlGaIn/GaN High-Electron-Mobility Transistors on Silicon Substrate. <i>IEEE Electron Device Letters</i> , 2012, 33, 1375-1377.	3.9	88
33	Influence of deep-pits on the device characteristics of metal-organic chemical vapor deposition grown AlGaIn/GaN high-electron mobility transistors on silicon substrate. <i>Applied Physics Letters</i> , 2011, 98, 252105.	3.3	29
34	Enhancement of breakdown voltage by AlN buffer layer thickness in AlGaIn-GaN high-electron-mobility transistors on 4in. diameter silicon. <i>Applied Physics Letters</i> , 2005, 86, 123503.	3.3	108
35	DC Characteristics in High-Quality AlGaIn/AlN/GaN High-Electron-Mobility Transistors Grown on AlN/Sapphire Templates. <i>Japanese Journal of Applied Physics</i> , 2005, 44, 6490-6494.	1.5	29
36	High-electron-mobility AlGaIn-AlN-GaN heterostructures grown on 100-mm-diam epitaxial AlN/sapphire templates by metalorganic vapor phase epitaxy. <i>Applied Physics Letters</i> , 2004, 85, 1710-1712.	3.3	89

#	ARTICLE	IF	CITATIONS
37	Valence-Band Discontinuity at the AlN/Si Interface. Japanese Journal of Applied Physics, 2003, 42, 6413-6414.	1.5	23
38	Improved dc characteristics of AlGaIn/GaN high-electron-mobility transistors on AlN/sapphire templates. Applied Physics Letters, 2002, 81, 1131-1133.	3.3	65
39	Thermal stability of GaN on (111) Si substrate. Journal of Crystal Growth, 1998, 189-190, 178-182.	1.5	167
40	Metalorganic Chemical Vapor Deposition and Material Characterization of Lattice-Matched InAlN/GaN Two-Dimensional Electron Gas Heterostructures. Applied Physics Express, 0, 1, 081102.	2.4	43
41	Simulation Study on Novel GaN-Based n^+p^n Heterojunction Bipolar Transistors with a Quaternary AlGaInN Emitter and a Two-Dimensionally Conductive Base. Physica Status Solidi (A) Applications and Materials Science, 0, , 2100397.	1.8	2